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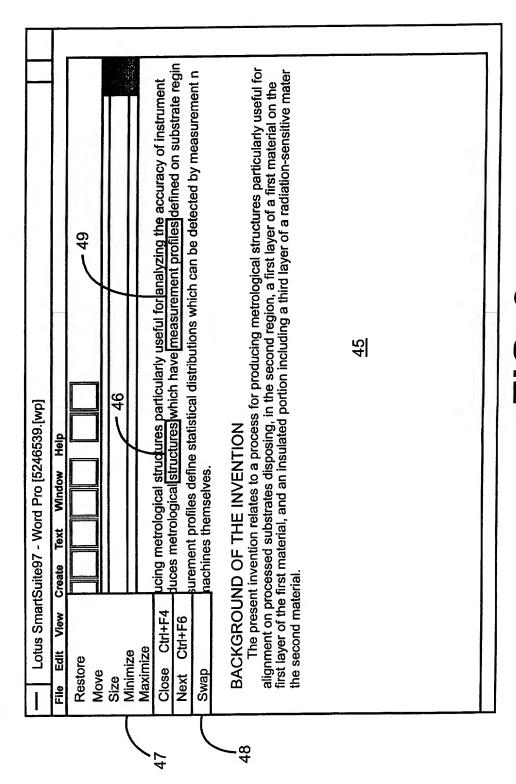
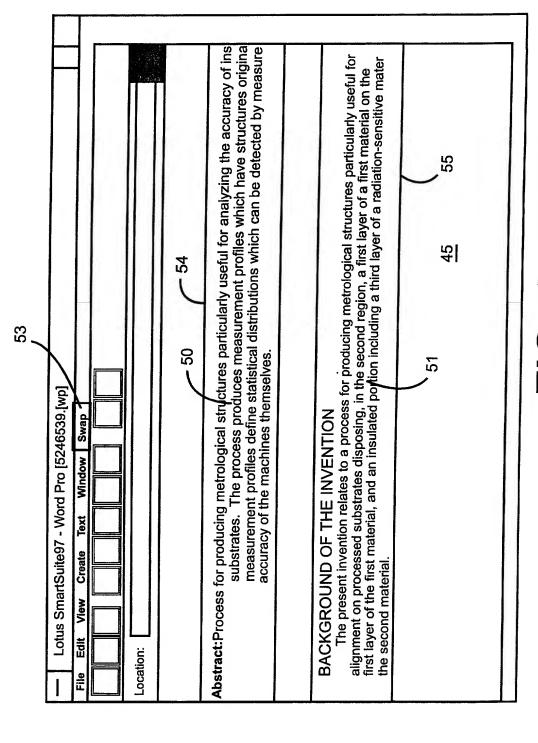


FIG. 2

— Lotus SmartSuite97 - Word Pro [5246539.[wp] File Edit View Create Text Window Help	Abstract: Process for producing metrological structures particularly useful for analyzing the accuracy of instrument The process produces metrological measurement profiles define statistical distributions which can be detected by measurement n accuracy of the machines themselves. BACKGROUND OF THE INVENTION The present invention relates to a process for producing metrological structures particularly useful for alignment on processed substrates disposing, in the second region, a first layer of a radiation-sensitive mater the second material.	45	

FG. 3



F|G. 4

FIG. 5

